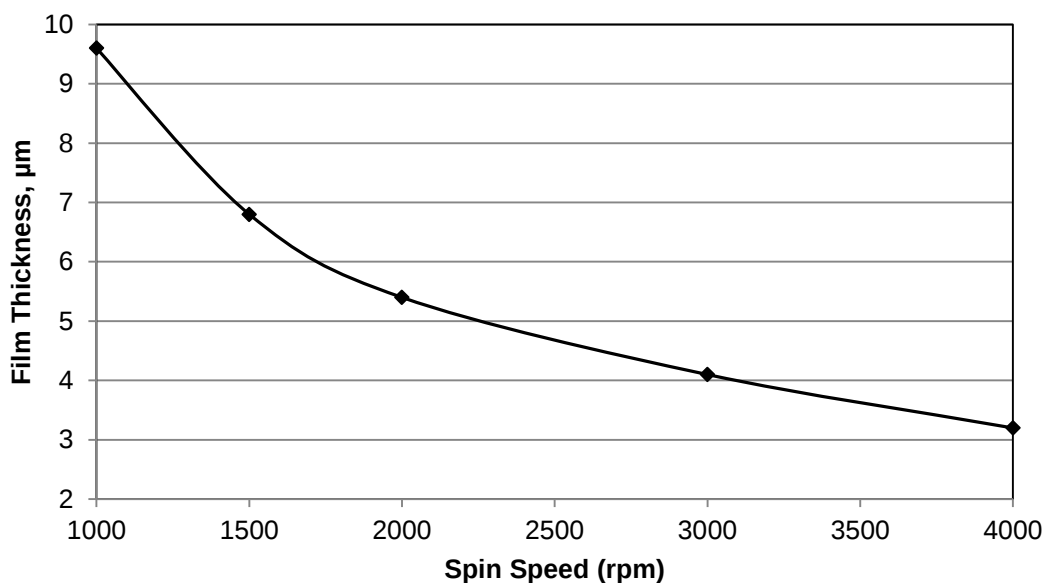


KMSF 1000

Processing Guide

- 1) Spin-coat (see spin speed curve below)- Recommended program:
 - a. Dispense 1ml of resist for each inch (25 mm) of substrate diameter.
 - b. Spin at 500 rpm for 5-10 seconds with acceleration of 500 rpm/second.
 - c. Spin at 1000-4000 rpm for 30 seconds with acceleration of 500 rpm/second.



- 2) Soft-bake: 100°C for 10 minutes on hotplate
- 3) Cool to room temperature
- 4) Exposure: Proximity Broadband > 400 mJ/cm²
- 5) Develop: KMSF Developer
 - a. Immersion Develop – 3-6 minutes, rinse with fresh developer
 - b. Spray Develop
 - i. Develop- 23°C, 70 rpm, 60 sec spay, 60 sec puddle + 60 sec spray
 - ii. Rinse- 23°C, 70 rpm, 10 sec. + 2000 rpm, 15 sec.
- 6) Hard Bake: 175°C/ 1 hr.